



Spacer

PRODUCT SPECIFICATION GUIDE

SPACER, NEUTRAL FILM

- NEUTRAL, DOES NOT ALTER SILICON SURFACE
- USED FOR ONE SIDE MASKING DURING SINGLE DOPING OF SILICON POWER DEVICE WAFERS
- OPERATING RANGE 1200 - 1300°C

PRODUCT	FILM APPLICATION/ NOTES
S100	•PARTICLE SIZE OF 35 - 44mm. •USED IN APPLICATIONS WHERE HIGH TEMPERATURE (>1300°C) AND RAPID SEPERATION IS REQUIRED •AVERAGE FILM THICKNESS 0.006"
S200	•PARTICLE SIZE OF 10 - 20mm. •USEFUL FOR COMPLETE PREVENTION OF DOPANTS PENETRATING FROM OTHER SIDE OF WAFER •AVERAGE FILM THICKNESS 0.004"

TABLE 1A CHEMICAL ANALYSIS	
SiO ₂	0.008%
Mn ₂ O ₃	0.001%
B ₂ O ₃	0.0001%
CaO	0.01%
Fe ₂ O ₃	0.005%
MgO	0.0015%
ZnO	0.001%
CuO	0.003%
Cr ₂ O ₃	0.001%
TiO ₂	0.0007%

AVAILABLE IN 3" AND 4" DIAMETERS